Appl. No. 10/698,198 Amd. Dated January 20, 2005 Reply to Office Action of October 6, 2004

## Amendments to the Specification:

Please replace the paragraph beginning at page 5, line 27, with the following amended paragraph:

Fig. 1 is a block diagram representation of a coarse stage and a fine stage which may be used as a part of an extreme ultraviolet lithography (EUVL) system in accordance with prior art.